

Resume format for Expert Listing in Nano Science and Technology

1. Name

ABHISHEK VIKRAM

2. Designation and Present Institution

Applications Manager,

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7. Brief account of my research interests with special focus on Nano Science and Technology

- Working in the semiconductor device research for nano-scale design.
- Worked on multiple joint research projects with IC design and manufacturing teams across the globe (IBM, Samsung, TI, TSMC, UMC, SMIC, etc) for development and evaluation of advanced process techniques to detect possible defects at an early stage of device design. This results in reliable and high chip yield.

Papers Published in International Magazines/Conferences:

1. Featured on cover page - Solid State Technology Magazine, June 2006:

Optimizing process window robustness with reconfigurable OPC – M

Anderson, A Vikram, W Volk, M Ma, S Andrews, B Su.

2. Proceedings of SPIE 6283, 62830Q(2006) (www.spiedl.org)

Lithography process window enhancement using integrated design defect

detection and fix - B Su, M Ma, A Vikram, W Volk, H Du, G Verma, R Morse, C Chu, B Tsao, C Lin, J Chou, and S Tsai

3. Yield Mgmt Solutions Magazine, Spring'06:

Bridging the gap between Design and Mask- Y F Cheng, Y L Chou, C H Yang, C L Lin, B Su, G Verma, W Volk, M Ahmadian, H Du, A Vikram, S Andrews

4. Proceedings of SPIE 6349, 634932(2006):

Polysilicon gate and polysilicon wire CD/EPE defect detection and classification through process window - S Andrews, W Volk, B Su, H Du, B Kumar, R Pusuluri, A Vikram, X Li, S Chen

5. Proceedings of SPIE 5992, 59921X(2005):

Applying reconfigurable RET across process window to create more robust manufacturing designs - M Laurance, A Vikram, M Ma, W Volk, M Anderson, S Andrews, B Su, H Du, and G Verma

6. Proceedings of SPIE 5992, 599244(2005):

Inspection of integrated circuit database through reticle and wafer simulation: the lithography process window performance monitoring - B Su, G Verma, W Volk, A Vikram, M Ahmadian, H Du, S Andrews, Y F Cheng, Y L Chou, C H Yang, and CL Lin

8. Keywords related to my research interests:

OPC (Optical Proximity Correction),
RET (Resolution Enhancement Technique),
Yield,
Pattern Based Grouping,
PRV (Post RET Verification),
Wafer Inspection,
MBOPC (Model Based OPC)